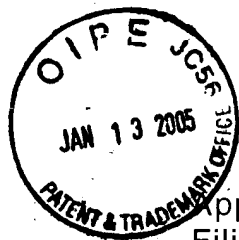


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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No.10/636,038
Filing DateAugust 6, 2003
Inventor..... Gurtej S. Sandhu
Assignee Micron Technology, Inc.
Group Art Unit 2824
Examiner Christian D. Wilson
Attorney's Docket No. MI22-2194
TitleMethods of Forming Material on a Substrate, and a Method of
Forming a Field Effect Transistor Gate Oxide on a Substrate

RESPONSE TO DECEMBER 30, 2004 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA EXPRESS MAIL

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Responsive to the Office Action dated December 30, 2004, Applicant
amends and remarks as follows:

AMENDMENTS